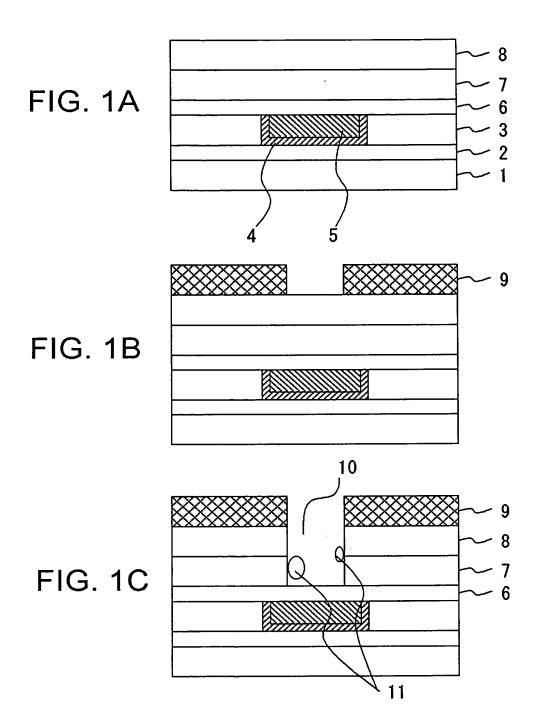
Docket No.: P8375.0002

App No.: Not Yet Assigned Docket No.: P8375.0 Inventor: Hidemitsu Aoki, et al.

Title: METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE AND APPARATUS FOR CLEANING SUBSTRATE

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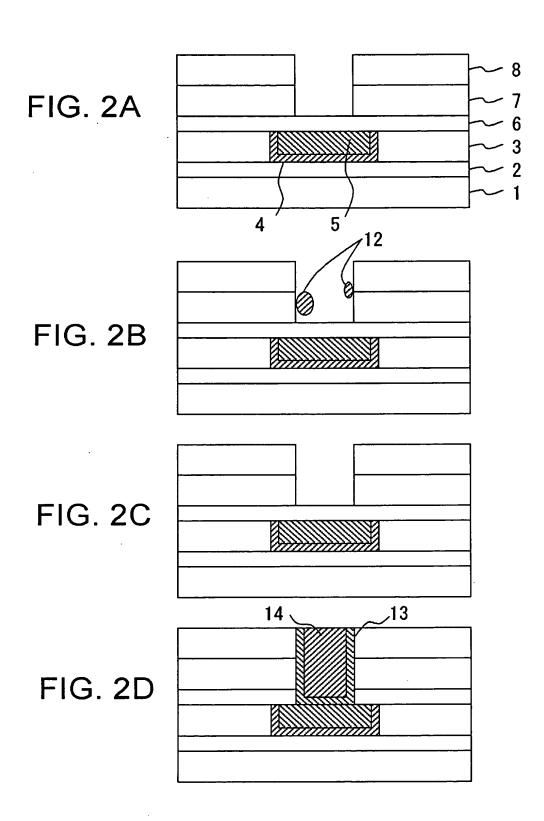


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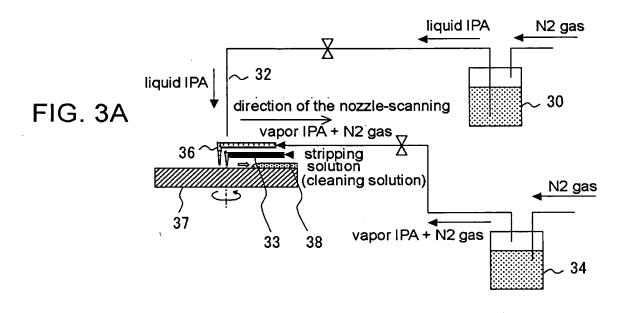
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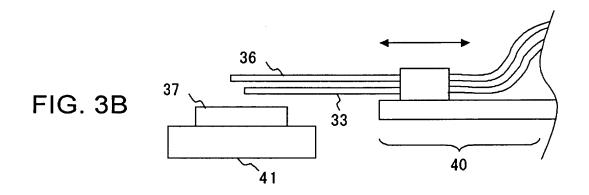
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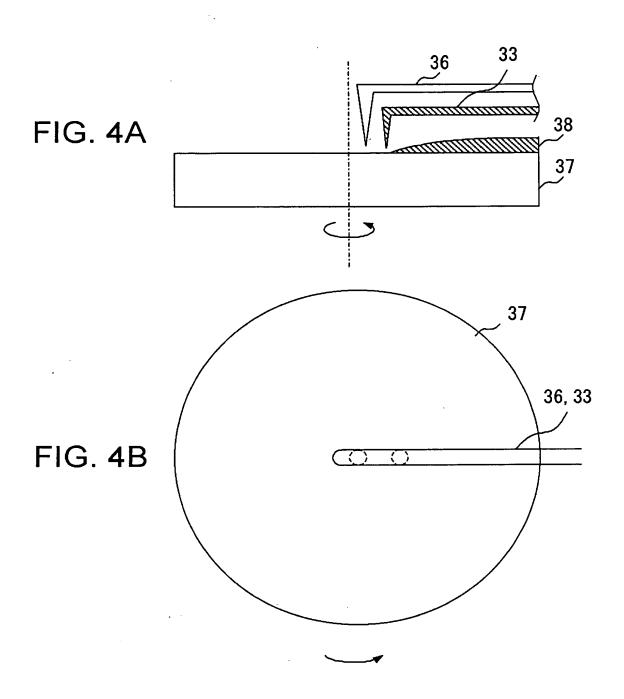




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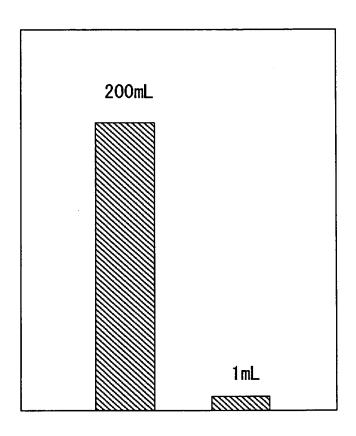
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FIG. 5

AMOUNTS OF **CONSUMED IPA** PER ONE WAFER



CONC. IPA **VAPOR IPA RINSE DRYING**

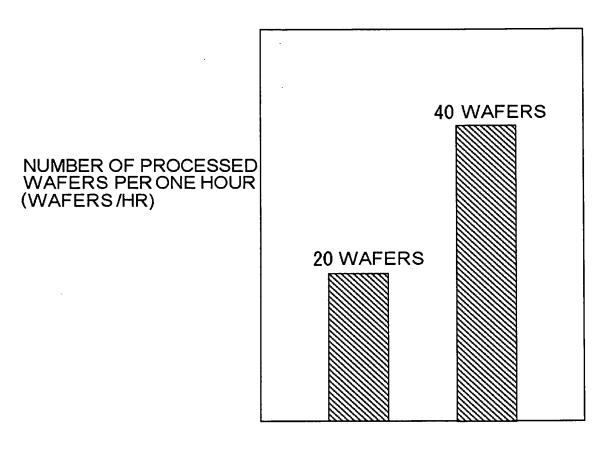
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FIG. 6

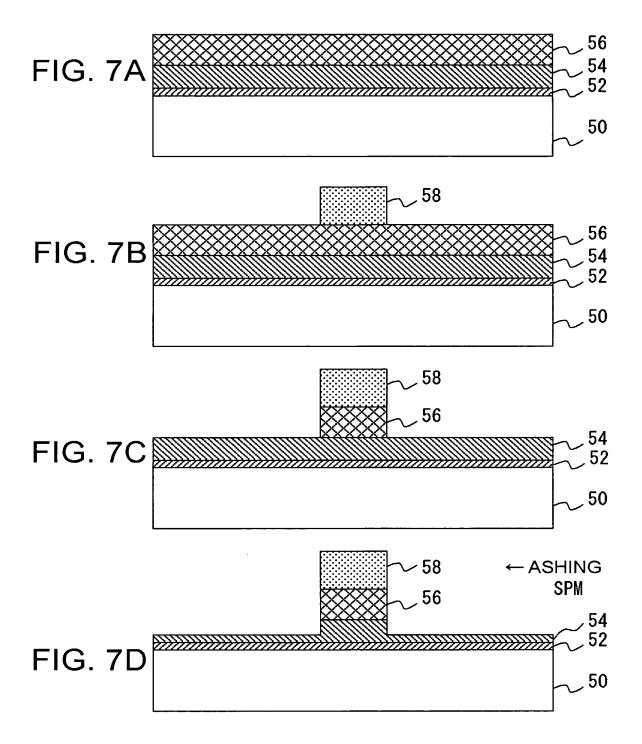


PURE WATER RINSE

VAPOR IPA DRYING

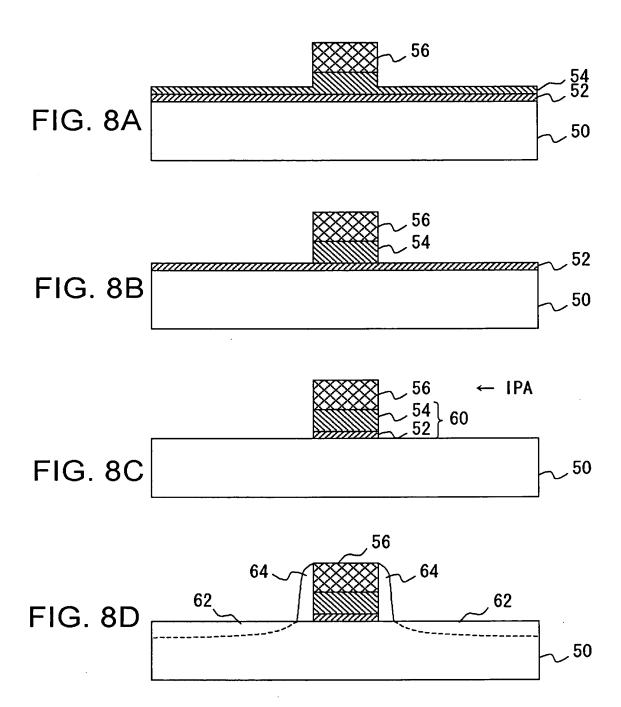
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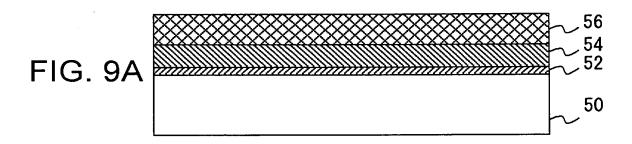
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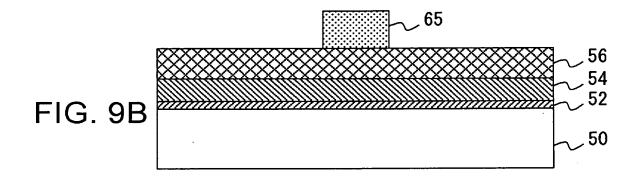


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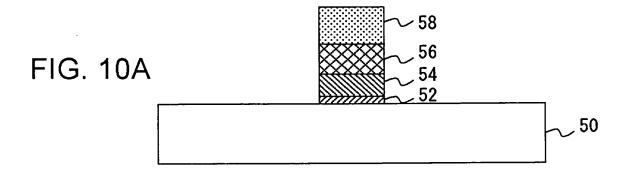
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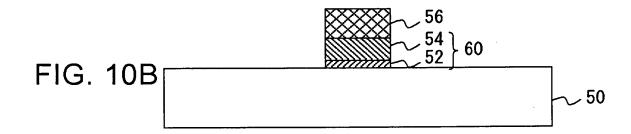


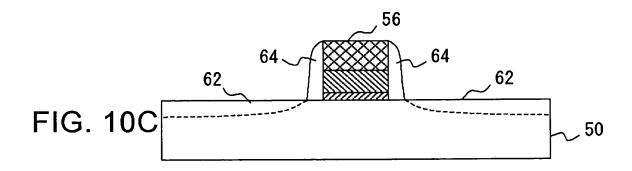


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Fig. 11A

	stripping agent	pure water rinse	1 ' '	nozzle scanning vapor IPA + Ilquid	nozzle scanning vapor IPA drying	N₂ gas dry (spinning drying)
No. 1 (Comparative Example)	1	2				3
No. 2	1		2			<u> </u>

Fig. 11B

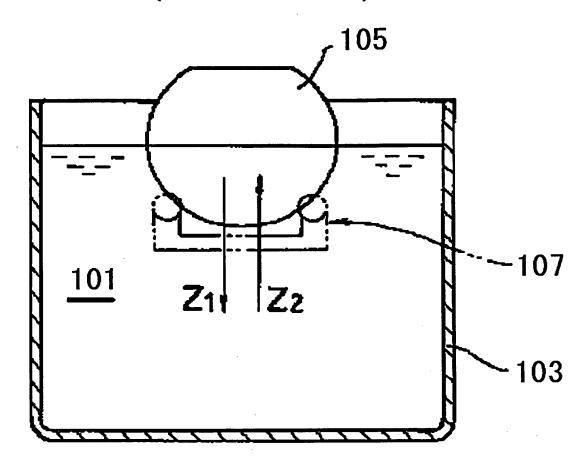
	stripping agent	pure water rinse	liquid IPA			nozzle scanning vapor IPA drying	N₂ gas dry (spinning drying)
No.3(Comparative Example)	1			2 (DIW)			3
No. 4	1				2		3

Fig. 11C

, ig. , i O							
	stripping age nt	pure water rinse	1 ' '	1	vapor IPA +	nozzle scanning vapor IPA drying	N ₂ gas dry (spinning drying)
No. 5(Comparative Example)	1	2				3	ļ
No. 6	1		2			3	
No. 7	1				2	3	
No. 8	1		2			3	4
No. 9	1			2(electrolyte-			3

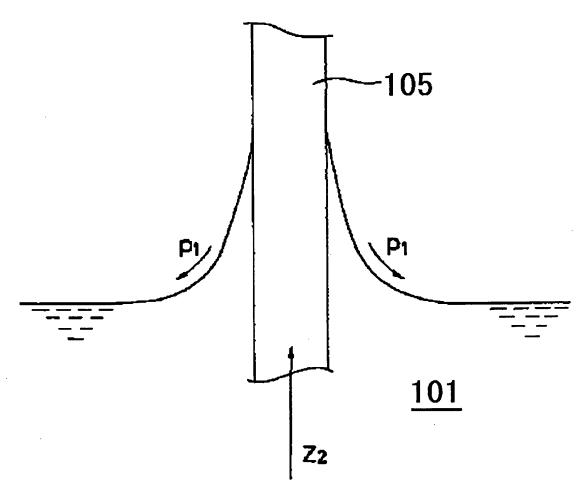
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FIG. 13 (PRIOR ART)



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FIG. 14A

upper surface



FIG. 14B

